







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| INFORMATION DISCLOSURE CITATION PTO-1449 | | Customer Number: 26615 | ATTORNEY'S DKT NO. H1172 | | APPLICATION NO. Unassigned | |
| | | | APPLICANT(S) 10/632,989 Srikanteswara Dakshina-Murthy et al. | | | |
| | | | FILING DATE August 4, 2003 | | GROUP Unassigned | |

| U.S. PATENT DOCUMENTS | | | | | | |
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| EXAMINER'S INITIALS | PATENT NO. | DATE | NAME | CLASS | SUBCLASS | FILING DATE |
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| FOREIGN PATENT DOCUMENTS | | | | | | | |
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| EXAMINER'S INITIALS | PATENT NO. | DATE | COUNTRY | CLASS | SUBCLASS | Translation | |
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| EXAMINER  | DATE CONSIDERED 6/20/04 |
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).